WHAT IS CLAIMED IS:

1. A low reflective antistatic hardcoat film comprising:

a transparent substrate film;

a transparent conductive layer formed on the transparent substrate film;

a hardcoat layer formed on the conductive layer; and

a low refractive layer formed on the hardcoat layer,

the low refractive layer having a lower refractive index than the hardcoat layer.

2. The low reflective antistatic hardcoat film according to claim 1, which has a surface resistivity of no more than 2×10^{12} $\Omega/\square$.

3. The low reflective antistatic hardcoat film according to claim 1, wherein the transparent conductive layer has a surface resistivity of no more than 10^{12} $\Omega/\square$.

4. The low reflective antistatic hardcoat film according to claim 1, which has a surface resistivity of no more than 2×10^{12} $\Omega/\square$ as measured in the form of a laminate of the transparent conductive layer and the hardcoat layer provided in that order on the transparent substrate film.

5. The low reflective antistatic hardcoat film according to claim 1, wherein the hardcoat layer has a volume resistivity in the direction of the thickness of no more than $10^8\,\Omega\cdot$cm.

6. The low reflective antistatic hardcoat film according to claim 1, wherein the hardcoat layer comprises a reaction curing resin composition.

7. The low reflective antistatic hardcoat film according to claim 6, wherein 10 to 100% by weight of the resin component in the reaction curing resin composition is accounted for by a reactive organosilicon compound.

8. The low reflective antistatic hardcoat film according to claim 1, wherein the hardcoat layer has a thickness of 1 to 50 μ m.

9. The low reflective antistatic hardcoat film according to claim 1, wherein the hardcoat comprises an anisotropic conductive layer of which the volume resistivity in the direction of the plane in the layer is higher than that in the layer thickness direction.

10. The low reflective antistatic hardcoat film according to claim 9, wherein the anisotropic conductive layer contains conductive fine particles.

11. The low reflective antistatic hardcoat film according to claim 10, wherein the conductive fine particles are organic beads which have been surface treated with gold and/or nickel.

12. The low reflective antistatic hardcoat film according to claim 1, wherein the low refractive layer comprises an inorganic compound layer.

13. The low reflective antistatic hardcoat film according to claim 12, wherein the inorganic compound layer comprises a layer of SiO_x wherein x is $1 \leqq x \leqq 2$.

14. The low reflective antistatic hardcoat film according to claim 12, wherein the low refractive layer has been formed by vacuum deposition.

15. The low reflective antistatic hardcoat film according to claim 1 or 9, wherein the hardcoat layer comprises a high refractive layer.

16. The low reflective antistatic hardcoat film according to claim 15, wherein the hardcoat layer contains high refractive ultrafine particles.

17. The low reflective antistatic hardcoat film according to claim 16, wherein the high refractive ultrafine particles have a particle diameter of 1 to 50 nm and a refractive index of 1.60 to 2.70.

18. The low reflective antistatic hardcoat film according to claim 1, wherein the low refractive layer comprises a layer formed by a sol-gel process.

19. The low reflective antistatic hardcoat film according to claim 18, wherein the layer formed by the sol-gel process is a layer of SiO_2 gel.

20. The low reflective antistatic hardcoat film according to claim 1, wherein the low refractive layer is a layer of an organic fluorocompound.

21. The low reflective antistatic hardcoat film according to claim 20, wherein the organic fluorocompound layer comprises a fluorinated vinylidene copolymer.